Temperature dependence of spin-dependent tunneling conductance for the parallel configuration of Co₂MnSi MTJs with high spin polarization

^oBing Hu, Kidist Moges, Hongxi Liu, Yusuke Honda, Tetsuya Uemura, and Masafumi Yamamoto

Graduate School of Science and Technology, Hokkaido University

E-mail: hu-bing@nsed.ist.hokudai.ac.jp

A highly efficient spin source is essential for spintronic devices. We recently showed that controlling defects through the film composition is critical to retain the half-metallicity of ternary Heusler alloy Co₂MnSi (CMS) and quaternary alloy Co₂(Mn,Fe)Si (CMFS) [1–3]. As a result, we demonstrated a giant TMR ratio of up to 2610% at 4.2 K (429% at 290 K) for CMS/MgO/CMS MTJs (CMS MTJs) and CMFS MTJs [1,3]. The purpose of the present study was to clarify the key mechanisms that determine the temperature dependence of the spin-dependent tunneling conductance G (= I/V), in particular, for the parallel configuration (P), G_P of CMS MTJs.

The preparation of fully epitaxial CMS MTJs with various values of α in Co₂Mn_{α}Si electrodes has been described elsewhere [1]. *G*_P was measured by a dc four-probe method at temperatures from 4.2 to 290 K at a small bias voltage of 2 mV. The TMR ratio was defined as TMR = $(G_P-G_{AP})/G_{AP}$.

Figure 1 plots the T dependence of the normalized G_P of CoFe-buffered CMS MTJs with various Mn compositions α in Co₂Mn_{α}Si_{0.84} electrodes. The TMR ratios at 4.2 K of these MTJs significantly increased with increasing α from 574% for Mn-deficient $\alpha = 0.73$ to 2011% for $\alpha =$ 1.30 [3]. G_P of these MTJs decreased with increasing T in a T range from T_1 (~25 K) to T_2 (~220 K). Then, it increased for $T > T_2$. Furthermore, the degree of the decrease in the normalized G_P at T_2 became larger for the MTJ that showed the larger TMR at 4.2 K. In contrast, the normalized GP of a CoFe/MgO/CoFe MTJ (CoFe MTJ) that showed a lower TMR of 382% at 4.2 K (258% at 290 K) slightly increased with increasing T from 4.2 K to around 100 K and then increased with T from around 100 K to 290 K. The T dependence of G_P of the CoFe MTJ can be explained by the Zhang's model in which a spin-flip, inelastic tunneling process via thermally excited magnon is taken into account [4]. Note that the Zhang's term provides an increase in G_P (and $G_{\rm AP}$) with increasing T.

To understand the *T* dependence of G_P of CMS MTJs with α from 0.73 to 1.30 that showed high TMR ratios ranging from 574% to 2011%, we take into consideration two tunneling processes; one is the Zhang's term [4] and another is the Shang's

term [5]. In the latter term, only spin-conserved elastic tunneling process is taken into account but the T dependence of spin polarization (SP) is introduced. Given this understanding, the $G_{\rm P}(T)$ for the CMS MTJs were fitted with the conductance at T = 0, and the additional terms from the Shang's process and the Zhang's process. This analysis is reasonable because the contribution to $G_{\rm P}$ from the Zhang's term decreases for MTJs with higher SP, resulting in a relative increase in the contribution of the Shang's term to $G_{\rm P}(T)$ for MTJs with higher SP. These fittings for the CMS MTJs well reproduced the experimental $G_P(T)$ with reasonable values of the parameters involved in the fitting. In conclusion, it was clarified that the characteristic Tdependence of CMS MTJs showing giant TMR ratios is highly influenced by the half-metallicity of the CMS electrodes.



Fig. 1. *T* dependence of the normalized tunneling conductance for the parallel configuration of CoFe-buffered CMS MTJS with various Mn compositions α in Co₂Mn_{α}Si_{0.84} electrodes ($\alpha = 0.73$, 1.24, 1.30). As a reference, *G*_P(*T*) for a CoFe MTJ is also plotted. The solid lines are fitted curves. The second to fourth curves from the bottom have respective offsets of 0.01 to 0.03 in the normalized *G*_P.

References

- [1] H. -x. Liu et al., APL **101**, 132418 (2012).
- [2] G. -f. Li et al., PRB **89**, 014428 (2014).
- [3] H. -x. Liu et al., J. Phys. D: Appl. Phys. 48, 164001 (2015).
- [4] S. Zhang et al., PRL **79**, 19 (1997).
- [5] C. H. Shang et al., PRB **58**, 2917(R) (1988).